

SUPPORTING INFORMATION

Hydrogen and Oxygen Evolution Reactions on Single Atom Catalysts Stabilized
by a Covalent Organic Framework

Ilaria Barlocco, Giovanni Di Liberto,* Gianfranco Pacchioni

Dipartimento di Scienza dei Materiali, Università degli Studi di Milano Bicocca, Via R. Cozzi 55

(20125) Milano, Italy

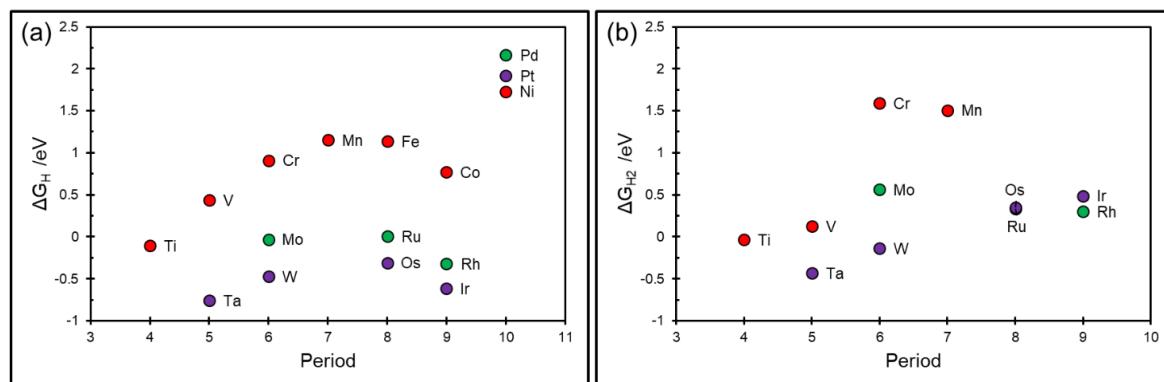
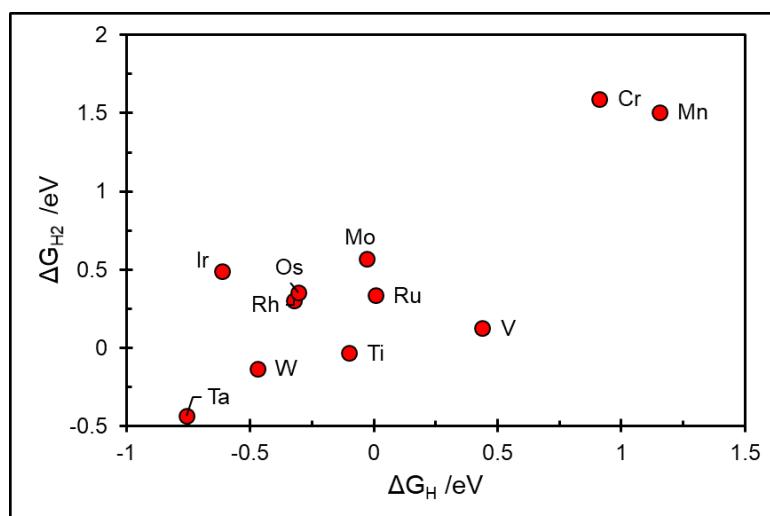


Figure S1: (a) Trend of reactivity to H^* vs TM group in the periodic table, (b) Trend of reactivity to H_2^* vs TM group in the periodic table.

Figure S2: Gibbs free energy of hydrogen complexes against that of H^* .



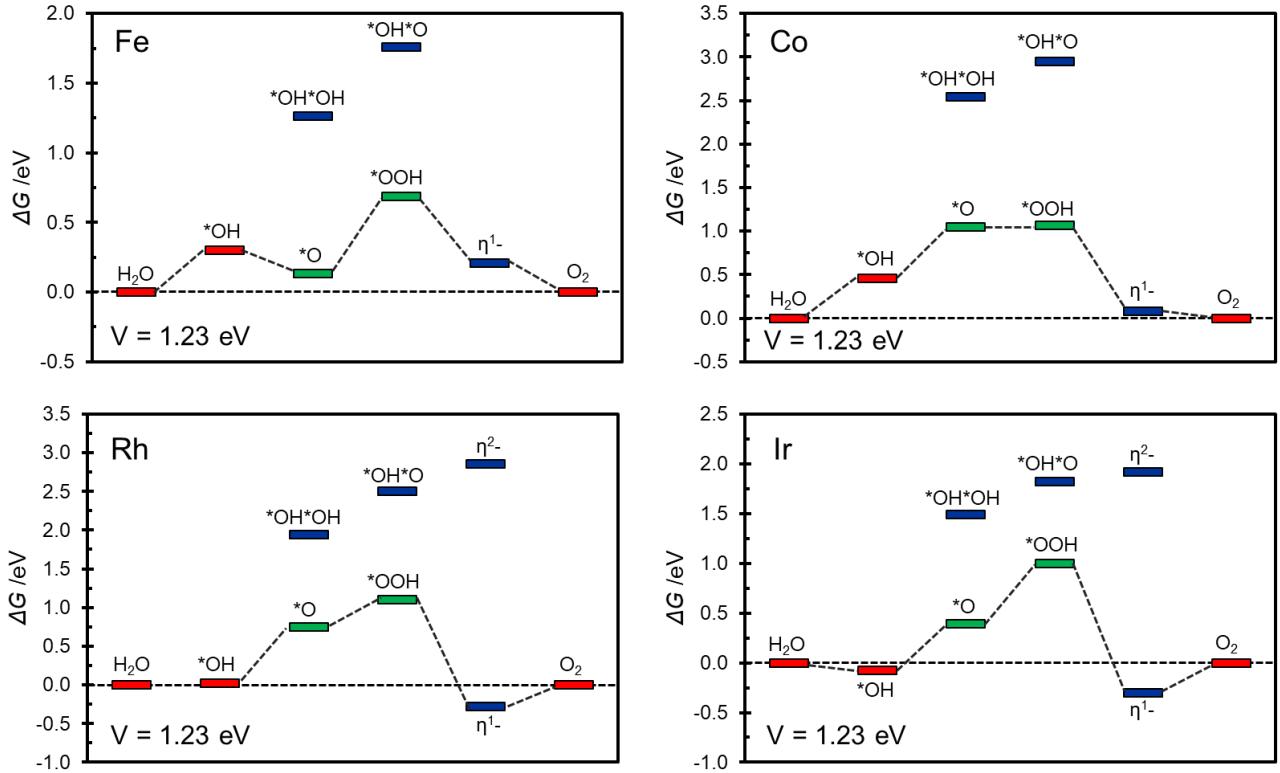


Figure S3: Gibbs Free Energy Profile of Fe, Co, Rh, and Ir SACs.

Table S1: Working entropic contributions of gas phase molecules at $T = 300\text{K}$.

Species	TS / eV
H_2	0.41
O_2	0.64
H_2O	0.67

Table S2: Calculated Zero-point energy of relevant reaction intermediates.

	ZPE_{OH^*}	ZPE_{O^*}	ZPE_{OOH^*}	$ZPE_{\eta 1}$	$ZPE_{\eta 2}$	$ZPE_{\text{OH}*\text{OH}^*}$	$ZPE_{\text{O}*\text{OH}^*}$
Mo	0.31	0.06	0.40	0.11	0.14	0.69	0.41
Ru	0.32	0.05	0.42	0.13	0.10	0.69	0.41
Rh	0.32	0.04	0.43	0.13	0.08	0.68	0.39
Average	0.32	0.05	0.41	0.12	0.11	0.69	0.40

The zero point contribution of H^* is often small, and typically value is 0.04 eV.¹

Table S3: Comparison of adhesion energies of different TMs on COF, N-doped graphene (4N-Gr) and carbon nitride (C_3N_4).

M	E_{ADH} (COF) /eV	E_{ADH} (4N-Gr) /eV	E_{ADH} (C_3N_4) /eV
Ti	-10.46	-8.50	-6.28
V	-10.13	-7.86	-5.05
Cr	-9.36	-7.20	-3.57
Mn	-8.24	-6.80	-3.36
Fe	-8.93	-7.39	-3.45
Co	-9.27	-7.79	-3.34
Ni	-9.46	-7.78	-3.47
Pd	-8.39	-6.03	-2.24
Pt	-10.58	-7.99	-2.79

Table S4: Gibbs free energies and O-O distances of the most stable oxygen complex intermediates for OER on TM@COF.

M	ΔG /eV	$d_{\text{O-O}}$ /Å	Isomer
Ti	1.27	1.46	η^2
V	--	--	--
Cr	4.53	1.29	η^1
Mn	4.71	1.30	η^1
Fe	5.12	1.28	η^1
Co	4.99	1.25	η^1
Ni	--	--	--
Nb	-0.02	2.58	η^2
Mo	0.76	2.55	η^2
Ru	4.38	1.29	η^1
Rh	4.63	1.27	η^1
Pd	--	--	--
Ta	-0.19	2.47	η^2
W	-0.43	2.60	η^2
Os	4.10	2.73	η^2
Ir	4.61	1.28	η^1
Pt	--	--	--

References

- 1 J. K. Nørskov, T. Bligaard, A. Logadottir, J. R. Kitchin, J. G. Chen, S. Pandelov and U. Stimming, *J. Electrochem. Soc.*, 2005, **152**, J23.